Amendments to the Specification:

Please amend the specification as follows:

Please replace paragraph [0001] on page 1 of the present Specification with the following rewritten paragraph:

[0001]	The present application	on is a continuation in-part application of <u>r</u>	<u>elated to</u>
U.S. Application	n Serial No. [[]] <u>10/341,863</u> , filed on [[]]
January 14, 200	3 by Ngo et al., entitled	d "Shallow Trench Isolation For Strained S	Silicon
Process" (Attorr	rey Docket No. 39153/	/639/HO963) and assigned to the Assignee	of the
present applicati	ion.		